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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet

1

U. S. PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
CY		US-4,757,207	07/1988	Chappelow et al	
		US-4,861,148	08/1989	Sato et al	
		US-4,929,083	05/1990	Brunner	
		US-5,124,927	06/1992	Hopewell et al	
		US-5,262,257	11/1993	Fukuda et al	
		US-5,285,236	02/1994	Jain	
		US-5,438,413	08/1995	Mazor et al	
		US-5,444,538	08/1995	Pellegrini	
		US-5,477,058	12/1995	Sato	
		US-5,700,602	12/1997	Dao et al	
		US-5,757,507	05/1998	Ausschnitt et al	
		US-5,805,290	09/1998	Ausschnitt et al	
		US-5,824,441	10/1998	Farrow et al	
		US-5,877,861	03/1999	Ausschnitt et al	
		US-5,953,128	09/1999	Ausschnitt et al	
↓		US-6,023,338	02/2000	Bareket	
		US-6,064,486	05/2000	Chen et al	
CY		US-6,079,256	06/2000	Bareket	

FOREIGN PATENT DOCUMENTS

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Examiner Signature	/Christopher Young/ (06/28/2006)	Date Considered	06/28/2006
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INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

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Sheet 2

of 8

Complete if Known

Application Number	10/765,223
Filing Date	01/26/2004
First Named Inventor	Smith et al
Art Unit	1756
Examiner Name	C. Young
Attorney Docket Number	38203-6081B

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CY		US-6,130,750	10/2000	Ausschnitt et al	
		US-6,137,578	10/2000	Ausschnitt	
		US-6,142,641	11/2000	Cohen et al	
		US-6,143,621	11/2000	Tzeng et al	
		US-6,153,886	11/2000	Hagiwara et al	
		US-6,163,366	12/2000	Okamoto et al	
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		US-6,218,200	04/2001	Chen et al	
		US-6,417,929	07/2002	Ausschnitt et al	
		US-6,737,207	05/2004	Imai	
		US-4,861,148	08/1989	Sato et al	
		US-6,573,986	06/2003	Smith et al	
		US-6,734,971	05/2004	Smith et al	
		US-6,906,303	06/2005	Smith	
		US-6,906,780	06/2005	Smith	
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CY		US-5,402,224	03/1995	Hirukawa et al	

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Attorney Docket Number	38203-6081B

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Signature /Christopher Young/ (06/28/2006)

Date Considered

06/28/2006

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INFORMATION DISCLOSURE
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Sheet 4

of 8

		Complete If Known	
Application Number		10/765,223	
Filing Date		01/26/2004	
First Named Inventor		Smith et al	
Art Unit		1756	
Examiner Name		C. Young	
Attorney Docket Number		38203-6081B	

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CY		Armitage et al, Analysis of overlay distortion patterns, SPIE Vol. 921, 207:221, 1988	
		Biesterbos et al., A New Lens for Submicron Lithography and its Consequences for Wafer Stepper Design, SPIE Vol. 633, Optical Microlithography V, 34:43, 1986	
		Bjorkholm et al., Reduction Imaging at 14nm Using Multilayer-Coated Optics: Printing of Features Smaller than 0.1 Micron, Journal Vacuum Science and Technology, B 8(6), 1509:1513, Nov/Dec 1990	
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		Dooly et al, Stepper Matching for Optimum Line Performance, SPIE Vol. 3051, 426:432, 1997	
↓		Goodwin et al, Characterizing Overlay Registration of Concentric 5X and 1X Stepper Exposure Fields Using Interfield Data, SPIE Vol. 3050, 407:417, 1997	
CY		Goodwin et al., Expanding Capabilities in Existing Fabs with Lithography Tool-Matching, Solid State Technology, 97:106, June 2000	

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Sheet 5

of 8

Complete If Known	
Application Number	10/765,223
Filing Date	01/26/2004
First Named Inventor	Smith et al
Art Unit	1756
Examiner Name	C. Young

Attorney Docket Number 38203-6081B

NON PATENT LITERATURE DOCUMENTS

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CY		Handbook of Microlithography, Micromachining and Microfabrication, Book: Vol. 1, "Microlithography", Rai-Choudhury, P. (Ed.), SPIE Optical Engineering Press, SPIE, Bellingham, Washington, pp. 417-418 (1997)	
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		Lin, "The Attenuated Phase-Shifting Mask", Solid State Technology, Special Series/Advanced Lithography, 35(1): 43-47 (1992)	
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		Filing Date	01/26/2004
		First Named Inventor	Smith et al
		Art Unit	1756
		Examiner Name	C. Young
Sheet	6	of	8
		Attorney Docket Number	
		38203-6081B	

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CY		McFadden, C. et al, A Computer Aided Engineering Workstation for Registration Control, SPIE Vol. 1087, 255:266, 1989	
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		Press et al., Numerical Recipes, The Art of Scientific Computing, Cambridge University Press, 52:64, 1990	
↓		Press et al., Numerical Recipes, The Art of Scientific Computing, Cambridge University Press, 509:520, 1990.	
CY		Progler et al., Method to Budget and Optimize Total Device Overlay, SPIE Vol. 3679, 193:207, 1999	

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Application Number	10/765,223
<i>(Use as many sheets as necessary)</i>		Filing Date	01/26/2004
		First Named Inventor	Smith et al
		Art Unit	1756
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Sheet	7	of	8
Attorney Docket Number 38203-6081B			

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CY		Quaestor Q7, "Fully Automated Optical Metrology System for Advanced IC Production", Quaestor Q7 Product Specification, BIO-RAD 2 pages
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CY		van den Brink et al., Matching Performance for Multiple Wafer Steppers using an Advanced Metrology Procedure, SPIE Vol. 921, 180:197, 1988

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Sheet 8

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Examiner Name	Unknown

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CY		van den Brink et al, New 0.54 Aperture I-Line Wafer Stepper with Field by Field Leveling Combined with Global Alignment, SPIE Vol. 1463, 709:724, 1991	
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		Zavecz, Life Beyond Mix-and-Match: Controlling Sub-0.18 Micron Overlay Errors, Semiconductor International, July 2000	
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